



MEXT (Ministry of Education, Culture, Sports, Science and Technology)
Knowledge Cluster Initiative (The Second Stage)
-Tokai Region Nanotechnology Manufacturing Cluster-



ISPlasma2010

2nd International Symposium on Advanced Plasma Science and its Applications
for Nitrides and Nanomaterials

March 7-10, 2010
Meijo University, Nagoya, Japan

Organizing Committee

Chairperson : Masaru Hori, Plasma Nanotechnology Research Center, Nagoya University
Vice-Chairperson : Hideki Masuda, Nagoya Institute of Technology
Hiroshi Amano, Meijo University
Keiji Nakamura, Chubu University

The ISPlasma is held as part of the Expansion Program of the Second Stage Knowledge Cluster Initiative (Tokai Region Nanotechnology Manufacturing Cluster) to establish an Advanced Plasma Nanotechnology Science Research Foundation in the Tokai region. The symposium will include invited lectures, selected oral/poster presentations and panel discussions.

SCOPE

The Symposium focuses on advanced plasma science and technology and its applications for nitrides and nanomaterials. A list of categories is given below.

- **Plasma Science and Technology**
(Plasma Measuring Technology/Simulation and Database/Etching Process/CVD Process/Solar Cells/Flexible Electronics/Plasma Applications)
- **Nitride Semiconductors**
(Bulk Growth/MBE Growth/Plasma Processing/Electronic Devices/White LEDs/UV LEDs)
- **Nanomaterials**
(Nanocarbon Materials/Solar Cells/Surface Modification/Surface Functionalization/Composite Materials/Functionally Graded Materials/Nanoparticles)
- **Integration Technology of Plasma Science, Nitride Semiconductors and Nanomaterials**
- **Industry-Government-Academia Collaboration**

ABSTRACT SUBMISSION

Each author is requested to submit a one-page abstract written in English.
All information regarding the abstract submission will be found on the website.

<http://www.isplasma.jp/>

Abstract Deadline: November 6, 2009

SPECIAL ISSUE

Selected papers will be published in a special issue of Jpn. J. Appl. Phys. (JJAP) and the instructions for submitting papers will be informed by the end of December.

Registration

Registration will open from 10, October, 2009

- **Registration Fee:**

Early Registration (before January 31st, 2010)	General : JPY 15,000	Student : JPY 3,000
Late Registration (until February 28th, 2010)	General : JPY 20,000	Student : JPY 5,000
- **Banquet Fee (on March 9th)**

	General : JPY 5,000	Student : JPY 2,000
--	----------------------------	----------------------------
- * Banquet fees must be paid at the time of registration.

Plenary / Keynote / Invited Speakers <Tentative>

Plasma Science

J. P. Chang (UCLA, USA)/U. Czarnetzki (Ruhr University, Bochum, GERMANY)/R. d'Agostino (University of Bari, ITALY)/M. Goeckner (University of Texas at Dallas, USA)/J. G. Han (CAPST, Sungkyunkwan University, KOREA)/M. Kushner (University of Michigan, USA)/O. Takai (Nagoya University, JAPAN)/T. Takamoto (SHARP CORPORATION, JAPAN)

Nitride Semiconductors

S. Arulkumaran (Nanyang Technological University, SINGAPORE)/B. Daudin (CEA Grenoble, FRANCE)/J. Y. Duboz (CNRS-CRHEA, FRANCE)/T. Egawa (Nagoya Institute of Technology, JAPAN)/T. Fukuda (Tohoku University, JAPAN)/U. Mishra (UCSB, USA)/S. Noda (Kyoto University, JAPAN)/K. Ota (TOYODA GOSEI Co., Ltd., JAPAN)/C. J. Sun (ITRI, TAIWAN)/T. Uesugi (Toyota Central R&D Labs., Inc., JAPAN)

Nanomaterials

S. Iijima (Meijo University, JAPAN)/S. Fukuzumi (Osaka University, JAPAN)/P. Milani (The University of Milan, ITALY)/J. Patscheider (EMPA, SWITZERLAND)/J. Robertson (Cambridge University, UK)/L. A. Rocha (University of Minho, PORTUGAL)/Y. Watanabe (Nagoya Institute of Technology, JAPAN)/Y. Wu (National University of Singapore, SINGAPORE)/T. Nozaki (Tokyo Institute of Technology, JAPAN)/T. Yoshida (Gifu University, JAPAN)

Industry -Government-Academia Collaboration

T. Higashi (Tokyo Electron Limited, JAPAN)/W. Izumiya (Sangyo Times, Inc., JAPAN)/E. Schultheiss (Fraunhofer Institute, GERMANY)

Panel Discussion <Tentative>

Application of Advanced Plasma Technology for Nitride Semiconductors

Y. Nanishi (Ritsumeikan University, JAPAN)/H. Amano (Meijo University, JAPAN)/B. Daudin (CEA Grenoble, FRANCE)/T. Hashizume (RCIQE, Hokkaido University, JAPAN)/H. Kano (NU Eco Engineering Co., LTD., JAPAN)/U. Mishra (UCSB, USA)/S. Noda (Kyoto University, JAPAN)

Application Front of Advanced Plasma Science and Industry -Government-Academia Collaboration

W. Izumiya (Sangyo Times, Inc., JAPAN)/M. Goeckner (University of Texas at Dallas, USA)/J. G. Han (CAPST, Sungkyunkwan University, KOREA)/M. Hori (Nagoya University, JAPAN)/S. Hosaka (Tokyo Electron Limited, JAPAN)/E. Schultheiss (Fraunhofer Institute, GERMANY)/M. Sato (MARUBUN CORPORATION, JAPAN)

Sponsored by : Aichi Science & Technology Foundation

Co-sponsored by : Aichi Prefecture, Nagoya City, Gifu Prefecture, Nagoya University, Nagoya Institute of Technology, Meijo University, Chubu University, The Japan Society of Applied Physics, The Japan Society of Plasma Science and Nuclear Fusion Research, The 162nd Committee on Wide Bandgap Semiconductor Photonic and Electronic Devices, Japan Society for the Promotion of Science

Contact

Secretariat for
ISPlasma2010 :
c/o Aichi Science &
Technology Foundation
Phone : +81-52-231-1656
Fax : +81-52-231-1640
E-mail: isplasma@astf.or.jp
<http://www.isplasma.jp/>